

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Gabric, <i>et al.</i>	Docket No.:	INF 2006 VJ 33543 US
Serial No.:	10/586,788	Art Unit:	TBD
Filed:	July 21, 2006	Examiner:	TBD
I.A. Filing Date:	January 22, 2005	I.A. No.:	PCT/DE2005/000088
For:	Plasma Excited Chemical Vapor Deposition Method Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly		

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Dear Sir:

Prior to examination on the merits, Applicant respectfully submits this Preliminary Amendment and remarks as set forth hereinafter.